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CERTIFICATE OF MAILING

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Richard A. Baumann

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Attorney Docket No. **NTI-019-2**

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application)

PATENT APPLICATION

Inventor(s): Christophe Pierrat et al.)

Art Unit: 2812

Application No.: 09/675,197)

Examiner: unknown

Filed: 09/29/2000)

Title "Dissection Of Edges With Projection Points In A)
Fabrication Layout For Correcting Proximity)
Effects)

INFORMATION DISCLOSURE STATEMENT UNDER 37 C.F.R. §1.97

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

Listed below or on an attached Form PTO-1449 is information known to applicant(s). A copy of each listed publication and U.S. and foreign patent, except for pending U.S. applications, is being submitted herewith, along with a concise explanation of information in a foreign language, if any, pursuant to 37 C.F.R. §1.97-1.98.

Applicants respectfully request that the listed information be considered by the Examiner and be made of record in the above-identified application. If form PTO-1449 is enclosed, the Examiner is requested to initial and return it in accordance with MPEP § 609.

This statement is not intended to represent that a search has been made or that the information cited in the statement is, or is considered to be, material to patentability as defined in 37 C.F.R. § 1.56.

- ☒ This statement qualifies under 37 C.F.R. § 1.97, subsection (b) because (check all that apply):
- ☐ (1) It is being filed within 3 months of the application filing date and is other than a continued prosecution application under § 1.53(d)
-- OR --
 - ☐ (2) It is being filed within 3 months of entry of a national stage
-- OR --
 - ☒ (3) It is being filed before the mail date of the first Office Action on the merits.
-- OR --
 - ☐ (4) It is being filed before the mailing of a first Office Action after the filing of a request for continued examination under § 1.114
- ☐ 37 C.F.R. § 1.97(c). If this statement is being filed after the period specified in § 1.97(b), but before the mailing date of the earlier of a final office action under § 1.113, a notice of allowance under § 1.311, or an action that otherwise closes prosecution in the application, then:
- ☐ a certification as specified in § 1.97(e) is provided below; **or**
 - ☐ a fee of \$180.00 as set forth in § 1.17(p) is authorized below, enclosed, or included with the payment of other papers filed together with this statement.
- ☐ 37 C.F.R. § 1.97(d). If this statement is being filed after the period specified in § 1.97(c), but on or before payment of the issue fee, then:
- A. a certification as specified in § 1.97(e) is completed below; **and**
 - B. a fee of \$180.00 as set forth in § 1.17(p) is authorized below, enclosed, or included with the payment of other papers filed together with this statement.
- ☐ *Fee Authorization.* The Commissioner is hereby authorized to charge the above-referenced fees of \$ 180 and charge any additional fees or credit any overpayment associated with this communication to Deposit Account No. 50-0574 (Docket No. NTI-019-2).

Respectfully submitted,

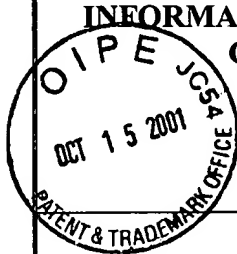
BEVER, HOFFMAN & HARMS, LLP

Dated: 10-11-01

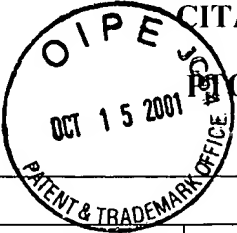
By: 
Jeanette S. Harms, Reg. No. 35,537

Telephone: (408) 451-5907
Customer No. 29477

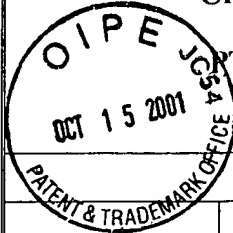
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INFORMATION DISCLOSURE CITATION  PTO-1449			ATTY. DOCKET NO. NTI-019-2		SERIAL NO. 09/675,197	
			APPLICANT Pierrat, et al.			
			FILING DATE 9/29/00		GROUP 2812	
U.S. PATENT DOCUMENTS						
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
	4,231,811	11/4/80	Somekh, et al.	148	1.5	9/13/79
	4,456,371	6/26/84	Lin	355	71	6/30/82
	4,902,899	2/20/90	Lin, et al.	250	492.1	6/1/87
	5,498,579	3/12/96	Borodovsky, et al.	437	250	6/8/94
	5,553,274	9/3/96	Liebmann	395	500	6/6/95
	5,636,002	6/3/97	Garofalo	355	53	10/31/95
	5,663,017	9/2/97	Schinella, et al.	430	5	6/7/95
	5,663,893	9/2/97	Wampler et al.	364	491	5/3/95
	5,723,233	3/3/98	Garza, et al.	430	5	2/27/96
	5,766,806	6/16/98	Spence	430	5	9/9/96
	5,821,014	10/13/98	Chen, et al.	430	5	2/28/97
	5,862,058	1/19/99	Samuels, et al.	364	491	5/16/96
	5,879,844	3/9/99	Yamamoto, et al.	430	30	12/20/96
	5,885,734	3/23/99	Pierrat, et al.	430	5	8/15/96
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	5,994,002	11/30/99	Matsuoka	430	5	9/4/97
	6,004,702	12/21/99	Lin	430	5	5/21/98
	6,077,310	6/20/00	Yamamoto, et al.	716	19	1/29/99
	6,078,738	6/20/00	Garza, et al.	395	500.22	5/8/97
EXAMINER			DATE CONSIDERED			


EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP § 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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			FILING DATE 9/29/00		GROUP 2812		
FOREIGN PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
	3-210560	9/13/91	JP			<input type="checkbox"/>	<input type="checkbox"/>
	8-236317	9/6/96	JP			<input type="checkbox"/>	<input type="checkbox"/>
	10-133356	5/22/98	JP			<input type="checkbox"/>	<input type="checkbox"/>
	11-143085	5/28/99	JP			<input type="checkbox"/>	<input type="checkbox"/>
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EXAMINER			DATE CONSIDERED				

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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)		
	Ackmann, P. et al., "Phase Shifting And Optical Proximity Corrections To Improve CD Control On Logic Devices In Manufacturing For Sub 0.35 μ m I-Line", Advance Micro Devices (8 pages).	
	Asai, N. et al., "Proposal For The Coma Aberration Dependent Overlay Error Compensation Technology", <i>Jpn. J. Appl. Phys.</i> , Vol. 37, pp. 6718-6722 (1998).	
	Chen, J.F. et al., "Full-Chip Optical Proximity Correction With Depth Of Focus Enhancement", <i>Microolithography World</i> (1997).	
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	Lin, B.J., "Methods To Print Optical Images At Low-k ₁ Factors", <i>SPIE</i> , Optical/Laser Microlithography III, Vol. 1264, pp. 2-13 (1990).	
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	Precim, "Proxima System", Precim Company, Portland, Oregon (2 pages).	
EXAMINER	DATE CONSIDERED	

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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)		
	Saleh, B. et al., "Reduction Of Errors Of Microphotographic Reproductions By Optimal Corrections Of Original Masks", <i>Optical Engineering</i> , Vol. 20, No. 5, pp. 781-784, September/October 1981.	
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